

Loading and unloading cycle for a CVD reactor system

Abstract

The invention relates to a device and a method for simultaneously coating a plurality of substrates (1, 9) in at least one process chamber (4) of a process chamber arrangement (21). It is essential, first, that after the coating the processed substrates (9) are alternately exchanged for unprocessed substrates in the process chamber. The subsequent coating process then occurs without prior cleaning of the process chamber. Three sets of the substrate carriers (2, 8) can be used simultaneously, such that, while a first set of the plurality of sets of the substrate carriers (2) is treated in at least one process chamber (4), a second set of the plurality of sets which contains unprocessed substrate carriers (2, 8) carrying unprocessed substrates (1) is disposed in at least one storage chamber (6, 7) of a storage chamber arrangement (19, 20) and a third set of the plurality of sets which contains processed substrate carriers (2, 8) carrying no substrates (1, 9) is disposed in the same or another storage chamber arrangement (19, 20) having at least one storage chamber (6, 7).

Fig. 11